

	Hits	Search Text	DBs
35	33	((substrate or wafer) same (panel\$3 or unit or clich\$2 or area or region or divid\$3) same (groove or etch\$2 or recess\$3 or raise\$2) same pattern\$4) and (((transfer\$3 near4 roll\$4) or (print\$4 near12 (cylinder or roll\$4))) same ((blanket or adhesive or adhesion) near12 (coat\$4 or film or layer)) same (resist or photoresist or (cur\$4 near12 (resin\$4 or material or composition or liquid))))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
36	6	((substrate or wafer) same (intaglio or panel\$3 or unit or clich\$2 or area or region or divid\$3) same (groove or etch\$2 or recess\$3 or raise\$2) same pattern\$4) and ((transfer\$3 or roll\$3 or collector or print\$4) same (blanket or film or layer or adhesion or adhesive) same (print\$3 near9 roll\$3) same (resist or photoresist or (cur\$4 near12 material))) and (((printing adj (roll or cylinder)) near12 blanket) same (pattern or resist or photoresist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
37	6	((substrate or wafer) same (intaglio or panel\$3 or unit or clich\$2 or area or region or divid\$3) same (groove or etch\$2 or recess\$3 or raise\$2) same pattern\$4) and ((transfer\$3 or roll\$3 or collector or print\$4) same (blanket or film or layer or adhesion or adhesive) same (print\$3 near9 roll\$3) same (resist or photoresist or (cur\$4 near12 material))) and (((printing adj (roll or cylinder)) near12 blanket) same (pattern or resist or photoresist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB